

# WEST Search History

DATE: Thursday, November 07, 2002

<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
side by side			result set
	<i>DB=USPT; PLUR=YES; OP=ADJ</i>		
L35	L16 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (temperature) near4 (control\$6 or regulat\$3 or alter\$3)) and ((chamber or wall or reactor or vessel or vessell) with temperature near4 (control\$5 or regulat\$4 or alter\$5))	5	L35
L34	L30 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (temperature) near4 (control\$6 or regulat\$3 or alter\$3)) and ((chamber or wall or reactor or vessel or vessell) with temperature near4 (control\$5 or regulat\$4 or alter\$5))	12	L34
L33	L30 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (chamber or wall or reactor or vessel or vessell) with (hotter or cooler or colder))	0	L33
L32	L30 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (chamber or wall or reactor or vessel or vessell) with (different or higher or lower) with (temperature))	12	L32
L31	L30 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3)) and ((chamber or wall or reactor or vessel or vessell) near3 (temperature or heat\$3 or cool\$3))	128	L31
L30	L29 not L7	3556	L30
L29	(ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5)))	3633	L29
L28	(ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5)))	3633	L28
	<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>		
L27	L26 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3)) and ((chamber or wall or reactor or vessel or vessell) near3 (temperature or heat\$3 or cool\$3))	201	L27
L26	L25 not L7	4055	L26
L25	(ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5)))	4183	L25
	<i>DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
L24	L21 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (chamber or wall or reactor or vessel or vessell) with (temperature) near4 (control\$6 or regulat\$3 or alter\$3))	3	L24
L23	L21 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (chamber or wall or reactor or vessel or vessell) with (hotter or cooler or colder))	0	L23
L22	L21 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (chamber or wall or reactor or vessel or vessell) with (different or higher or lower) with (temperature))	2	L22

L21	(ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5)))	1550	L21
	<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>		
L20	L16 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (chamber or wall or reactor or vessel or vessel) with (temperature) near4 (control\$6 or regulat\$3 or alter\$3))	10	L20
L19	L16 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (chamber or wall or reactor or vessel or vessel) with (hotter or cooler or colder))	1	L19
L18	L16 and ((substrate or wafer or pedestal or chuck or sample or support\$3) with (chamber or wall or reactor or vessel or vessel) with (different or higher or lower) with (temperature))	10	L18
L17	L16 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3)) and ((chamber or wall or reactor or vessel or vessel) near3 (temperature or heat\$3 or cool\$3))	78	L17
L16	(ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5))) and L7	128	L16
	<i>DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
L15	L14 not L13	12	L15
L14	L12 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3)) and ((wall or chamber or reactor or vessel or vessel) near3 (temperature or heat\$3 or cool\$3))	15	L14
L13	L12 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3)) and ((wall) near3 (temperature or heat\$3 or cool\$3))	3	L13
L12	(ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5)))	1550	L12
	<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>		
L11	L8 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3)) and ((wall) near3 (temperature or heat\$3 or cool\$3))	69	L11
L10	L8 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3)) and ((chamber or wall or reactor or vessel or vessel) near3 (temperature or heat\$3 or cool\$3))	209	L10
L9	L8 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3)) and ((chamber or wall or reactor or vessel or vessel) near6 (temperature or heat\$3 or cool\$3))	234	L9
L8	L7 and (ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5)) or (vapor near2 epitax\$5))	362	L8
L7	L5 or L6	5862	L7
L6	((118/724).icls. or ((118/725)!.ICLS. ))	1738	L6
L5	((427/248.1).icls. or (427/255.23).icls. or (427/255.28).icls. or (427/255.7).icls. or (427/587).icls. or (118/715).icls. or (118/719).icls. or (118/728).icls. or (117/84).icls. or (117/88).icls. or ((117/105	5064	L5

)!.ICLS. ))

*DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ*

L4	L3 and (temperature or heat\$3 or cool\$3 or hot or cold)	9	L4
L3	(Lindfors or Bondestam or ASM) and (ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5)))	23	L3

*DB=USPT,PGPB; PLUR=YES; OP=ADJ*

L2	L1 and ((substrate or wafer or pedestal or chuck or sample or support\$3) near4 (temperature or heat\$3 or cool\$3 or hot or cold)) and ((chamber or wall or reactor or vessel or vessel) near6 (temperature or heat\$3 or cool\$3 or hot or cold))	10	L2
L1	(Lindfors.in. or Bondestam.in. or ASM.as.) and (ALE or ALD or (atomic layer near2 (deposit\$4 or epitax\$5)))	18	L1

END OF SEARCH HISTORY